

Acknowledgment to the Reviewers of *ChemEngineering* in 2022

ChemEngineering Editorial Office

MDPI AG, St. Alban-Anlage 66, 4052 Basel, Switzerland

High-quality academic publishing is built on rigorous peer review. *ChemEngineering* was able to uphold its high standards for published papers due to the outstanding efforts of our reviewers. Thanks to the efforts of our reviewers in 2022, the median time to first decision was 14 days and the median time to publication was 44 days. Regardless of whether the articles they examined were ultimately published, the editors would like to express their appreciation and thank the following reviewers for the time and dedication that they have shown *ChemEngineering*:

Abdulgalim, Isaev
Agata, Małysiak
Ahmed K., Badawi
Aida Maria, Diez Sarabia
Akira, Morikawa
Ákos, Kuki
Alejandro, Medina
Alex Fan, Xu
Alexander M., Volodin
Alexander, Wittemann
Alina, Kowalczyk-Juśko
Amitava, Moulick
Amr, Fouda
Ana Sofia, Dias Mestre
Ananthakumar, Ramadoss
Andras, Erdohelyi
Andrea, Ragusa
Andreas, Jess
Andrew C., Chien
Anna, Fajdek-Bieda
Anna, Wołowicz
Anton, Petukhov
Antonello, Barresi
Antonije, Onjia
Antonio Jose, Exposito
Antonio, Gagliano
Artem, Belousov
Aurelian Cristian, Boscornea
Ayman, Youssef
Aymen, Assadi
Barbara, Sacchi
Bartłomiej, Zieniuk
Benedikt, Hülsemann
Benyoucef, Abdelghani

Biljana, Abramović
Boubié, Guel
Bruno Sena, Da Fonseca
Carmen, Zaharia
Chandra Mouli R., Madhuranthakam
Chetna, Mohabeer
Chuanyu, Sun
Cláudio, Rocha
Cristian, Barca
Cristian, Simion
Daniel, Mamais
Danilo, Escobar-Avello
Dattatraya, Subhedar
Davide, Clematis
Depei, Zhang
Dirk, Tischler
Doina, Humelnicu
Domenico, Flagiello
Domingo, Martín
Donato, Fontanarosa
Dong Jin, Yoo
Duong, Nguyen
Ece, Polat
Elena, López-Maya
Elmar, Villota
Emanuel M., Fernandes
Emerson H., De Faria
Emma, Palo
Enrico, Andreoli
Ermelinda, Falletta
Esin, Varol
Eva Oktavia, Ningrum
Federica, Turrini
Felix, Brück

Citation: *ChemEngineering* Editorial Office. Acknowledgment to the Reviewers of *ChemEngineering* in 2022. *ChemEngineering* **2023**, *7*, 9. <https://doi.org/10.3390/chemengineering7010009>

Published: 18 January 2023



Copyright: © 2023 by the authors. Licensee MDPI, Basel, Switzerland. This article is an open access article distributed under the terms and conditions of the Creative Commons Attribution (CC BY) license (<http://creativecommons.org/licenses/by/4.0/>).

Fiderman, Machuca-Martínez
Filipe Hobi Bordón, Sosa
Filippo, Samperi
Ghanshyam Singh, Chauhan
Ghulam, Ali
Godvin Sharmila, V.
Gospodinka, Gicheva
Govindasamy, Mani
Granch, Berhe Tseghai
Grażyna, Wejnerowska
Guixia, Zhao
Guoqin, Huang
Hak Joo, Kim
Hamid, Eisazadeh
Hangfeng, Zhang
Hasi Rani, Barai
Heitor, Bento
Hongfei, Ma
Hugo A. L., Filipe
Hugo, Rojas-Chávez
Igor M., Piskarev
Igor, Prikhodko
Igor, Schreiber
Ionuț, Banu
Iqrash, Shafiq
Irene Samy, Fahim
Irene, Tagliaro
Islam, Md. Aminul
Ivalina, Avramova
Jacek, Andrzejewski
Jakub, Mokrzycki
Jayanthi, Kumar
Jenshinn, Lin
Jinbo, Fei
Joanna, Piotrowska-Woroniak
Jorg, Thöming
Jorge L., Folch-Mallol
Joshua, Van Der Zalm
Józef, Haponiuk
Junghwan, Kim
Kai, Wang
Katarzyna, Cieślak
Kingo, Ariyoshi
Kirill M., Skupov
Kondo-Francois, Aguey-Zinsou
Krzysztof, Formela
Krzysztof, Kruczala
Kumarasamy, Sudhakar
Ladislav, Lukáč
Lahoucine, Bahsis
Lalit R, Kumar
Lei, Li
Leszek, Kadziński
Liangjun, Xia
Liliana, Lazar
Lorenzo, Guazzelli
Louis Wy, Liu
Luciano C., Almeida
Luguang, Wang
Luis F., Bobadilla
Macarena, Gómez-Mármol
Madalina, Ciobanu
Magdalena, Gizowska
Magdalena, Zdanowicz
Maqsood, Malik
Marcia Regina, Assalin
Marcin K., Wojs
Marco, Vaccari
Marcos F. S., Teixeira
Marek, Ochowiak
Maria Emilia, Brassesco
Maria, Portarapillo
Maria, Ricciardi
Maria, Włodarczyk-makula
Mariateresa, Lettieri
Marica, Muscetta
Marina G., Khmeleva
Marta, Stucchi
Martin, Carlos
Márton, Szabados
Marvin, Ricaurte
Mauricio, Patón
Mengmeng, Zhang
Miguel, Menéndez
Mikhail A., Il'yushin
Ming, Jiang
Minh Vien, Le
Miroslav, Variny
Mohamad Fakhurul Ridhwan, Samsudin
Mohammad A., Hasnat
Monica Francesca, Pucci
Moro, Daniele
Mousumi, De Sarkar
Muhammad Syafiq Hazwan, Ruslan
Muhammad, Tahir
Murali, Dama
Natalija, Velić
Natasa, Nastic
Neli, Mintcheva
Nicolae, Gica
Nikolay, Rodkevich
Norshahidatul Akmar Mohd, Shohaimi

Nouf Faisal, Alharby	Sonal V., Bhujbal
Olvier, Aubry	Srikanth, Vuppala
Oussama, Baaloudj	Sriram, Ganesan
Palani, Molaiyan	Stefan, Jopp
Paola, Sangiorgio	Stefan, Krakowiak
Patrick, Lott	Supriya, Chavan
Paweł, Grabowski	Susan E., Henkelis
Payam, Sarir	Sylwester, Furmaniak
Peng, Du	Szabolcs, Muráth
Peng, Li	Thais, Milessi
Petar, Varbanov	Thanh Tin, Nguyen
Peter, Lang	Thomas, Waluga
Petr, Šálek	Timothy, Hunter
Peyman Roudgar, Saffari	Tomasz A., Prokop
Pietro, Ballone	Ufuk, Malayoglu
Polina, Tyubaeva	Valerio, Paolini
Pothiappan, Vairaprakash	Vamsee, Vadlamudi
Preety, Ahuja	Vasile, Lavric
Przemyslaw, Bartczak	Vikram Uttam, Pandit
Qiang, Chen	Vincenzo A., Riggio
Qicheng, Feng	Wei, Luo
Radek, Šulc	Wenjia, Wang
Rafik, Saddik	Weon Bae, Ko
Rahul, Kavthe	Xiaojun, Liu
Rajesh, Haldhar	Xin, Gao
Ramona, Kuhn	Xinquan, Cheng
Reda, Elkacmi	Yifeng, Tian
Rika, Ochi	Yong, Ren
Rodrigo Sávio, Pessoa	Yu-Chun, Chiang
Rosalinda, Inguanta	Yueping, Wang
Sanjeev Kumar, Ujjain	Yung-Ching, Ding
Savelii, Kukharets	Yunxiang, Xie
Sayan, Banerjee	Yuxi, Xie
Shahabaldin, Rezanian	Zaida, Ortega
Shuai, Qian	Zengqian, Shi
Shuai, Wang	Zheng, Zhou
Silvia, Vasiliu	Zhigang, Zang
Simone, Rossi	Zhuolin, Ye
Sinan, Kutluay	Zupeng, Chen
Sivasankar, Annamalai	

Disclaimer/Publisher's Note: The statements, opinions and data contained in all publications are solely those of the individual author(s) and contributor(s) and not of MDPI and/or the editor(s). MDPI and/or the editor(s) disclaim responsibility for any injury to people or property resulting from any ideas, methods, instructions or products referred to in the content.